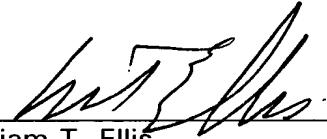


Appl. No. Unassigned

**REMARKS**

Applicant respectfully requests that the foregoing amendments to Claims 18 and 20 be made prior to examination of the present application.

Respectfully submitted,



William T. Ellis  
Attorney for Applicant  
Registration No. 26,874

November 8, 2001  
Date

FOLEY & LARDNER  
Customer Number: 22428



22428

PATENT TRADEMARK OFFICE

Telephone: (202) 672-5485  
Facsimile: (202) 672-5399

**VERSION WITH MARKINGS TO SHOW CHANGES MADE**

18. (Amended) The projection exposure method [as claimed in any one of claims 10 to 16] according to claim 10, wherein, in said second step, said substrate is irradiated with exposure light of said appropriate intensity by changing an interval between pulse light emissions of said exposure light.

20. (Amended) A semiconductor device fabricated by use of the projection exposure method according to claim[s] 10.

PRINTED IN U.S.A. 002.663416.1